2023년 2월 14일(화), 09:00-10:45
Room A (에메랄드 I, 5층)

D. Thin Film Process Technology 분과
[TA1-D] Metallic Films

좌장: 김성근 책임연구원(한국과학기술연구원), 엄태용 임연구원(한국화학연구원)

TA1-D-1 **09:00-09:30** **[초청]**	**반도체 소자에서 구리 범프와 절연 고분자의 하이브리드 본딩** 심영주, 김한글, 황경석, 김주영 *울산과학기술원 신소재공학과*
TA1-D-2 **09:30-09:45**	**Molybdenum Carbide Thin Films Deposited by Thermal Atomic Layer Deposition Method under Thermal Decomposition of Mo Precursor** Min-Ji Ha, Jeong-Hun Choi, and Ji-Hoon Ahn *Department of Materials Science and Chemical Engineering, Hanyang University*
TA1-D-3 **09:45-10:00**	**Composition and Work Function Tuning of Plasma-enhanced Atomic-layer Deposited MoC_xN_y Films** Ji Sang Ahn, Wangu Kang, and Jeong Hwan Han *Department of Materials Science and Engineering, Seoul National University of Science and Technology*
TA1-D-4 **10:00-10:15**	**Modified Atomic Layer Deposition of Low-resistivity Molybdenum Carbide and Nitride Electrode for Next Generation DRAM Capacitor** Wangu Kang, Ji Sang Ahn, and Jeong Hwan Han *Department of Materials Science and Engineering, Seoul National University of Science and Technology*
TA1-D-5 **10:15-10:30**	**Atomic Layer Etching of Ruthenium Films with Organic Precursor** Jeongbin Lee, Jung-Tae Kim, and Woo-Hee Kim *Department of Materials Science and Chemical Engineering, Hanyang University*
TA1-D-6 **10:30-10:45**	**Growth Characteristics of Atomic Layer Deposited Iridium Thin Films with TICP and Oxygen** Hong Keun Chung[1,2], Tae Joo Park[2], and Seong Keun Kim[1,3] *[1]Electronic Materials Research Center, KIST, [2]Department of Materials Science and Chemical Engineering, Hanyang University, [3]KU-KIST Graduate School of Converging Science and Technology, Korea University*